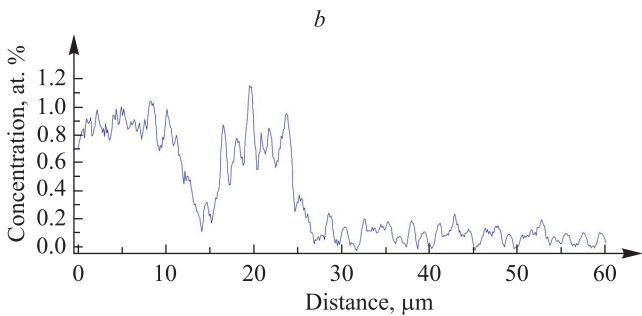
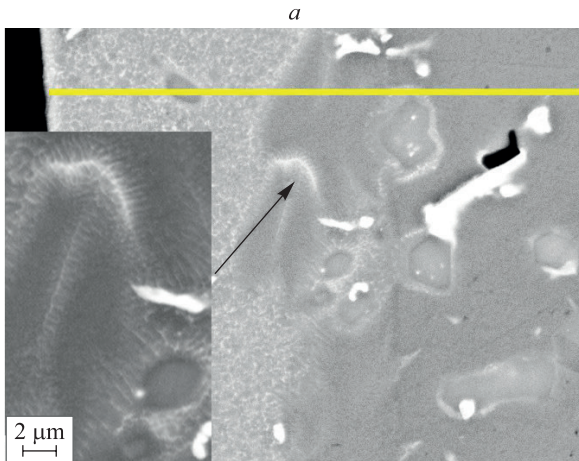


Fig. 4. Cross-section morphology (*a*), distribution of titanium (*b*) and silicon (*c*) along the depth of the surface layer in a sample treated with CPF at 35 J/cm^2